

Vincent Vandalon

List of Publications by Year in descending order

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1151
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#	ARTICLE	IF	CITATIONS
1	Surface Chemistry during Atomic Layer Deposition of Pt Studied with Vibrational Sum-Frequency Generation. <i>Journal of Physical Chemistry C</i> , 2022, 126, 2463-2474.	3.1	7
2	Controlling transition metal atomic ordering in two-dimensional $\text{MoS}_2/\text{WSe}_2$ alloys. <i>2D Materials</i> , 2022, 9, 025016.	4.4	9
3	Influence of the spatial extent of the space-charge region in c-Si on the electric-field-induced second-harmonic-generation effect. <i>Journal of the Optical Society of America B: Optical Physics</i> , 2021, 38, 1840.	2.1	1
4	Atmospheric-Pressure Plasma-Enhanced Spatial ALD of SiO_2 Studied by Gas-Phase Infrared and Optical Emission Spectroscopy. <i>Journal of Physical Chemistry C</i> , 2021, 125, 24945-24957.	3.1	9
5	Probing the Origin and Suppression of Vertically Oriented Nanostructures of 2D WS_2 Layers. <i>ACS Applied Materials & Interfaces</i> , 2020, 12, 3873-3885.	8.0	22
6	Atomic Layer Deposition of Al-Doped MoS_2 : Synthesizing a p-type 2D Semiconductor with Tunable Carrier Density. <i>ACS Applied Nano Materials</i> , 2020, 3, 10200-10208.	5.0	22
7	Large area, patterned growth of 2D MoS_2 and lateral MoS_2/WS_2 heterostructures for nano- and opto-electronic applications. <i>Nanotechnology</i> , 2020, 31, 255603.	2.6	46
8	Initial Growth Study of Atomic-Layer Deposition of Al_2O_3 by Vibrational Sum-Frequency Generation. <i>Langmuir</i> , 2019, 35, 10374-10382.	3.5	16
9	Infrared and optical emission spectroscopy study of atmospheric pressure plasma-enhanced spatial ALD of Al_2O_3 . <i>Applied Physics Letters</i> , 2019, 115, 083101.	3.3	11
10	Edge-Site Nanoengineering of WS_2 by Low-Temperature Plasma-Enhanced Atomic Layer Deposition for Electrocatalytic Hydrogen Evolution. <i>Chemistry of Materials</i> , 2019, 31, 5104-5115.	6.7	57
11	Sticking probabilities of H_2O and $\text{Al}(\text{CH}_3)_3$ during atomic layer deposition of Al_2O_3 extracted from their impact on film conformality. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	2.1	30
12	Polarized Raman spectroscopy to elucidate the texture of synthesized MoS_2 . <i>Nanoscale</i> , 2019, 11, 22860-22870.	5.6	13
13	Chemical Analysis of the Interface between Hybrid Organic-Inorganic Perovskite and Atomic Layer Deposited Al_2O_3 . <i>ACS Applied Materials & Interfaces</i> , 2019, 11, 5526-5535.	8.0	40
14	Low-temperature plasma-enhanced atomic layer deposition of 2-D MoS_2 : large area, thickness control and tuneable morphology. <i>Nanoscale</i> , 2018, 10, 8615-8627.	5.6	90
15	Plasma-enhanced atomic layer deposition of tungsten oxide thin films using $(\text{tBuN})_2(\text{Me}_2\text{N})_2\text{W}$ and O_2 plasma. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, .	2.1	26
16	Simultaneous scanning tunneling microscopy and synchrotron X-ray measurements in a gas environment. <i>Ultramicroscopy</i> , 2017, 182, 233-242.	1.9	8
17	Revisiting the growth mechanism of atomic layer deposition of Al_2O_3 : A vibrational sum-frequency generation study. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	2.1	41
18	What is limiting low-temperature atomic layer deposition of Al_2O_3 ? A vibrational sum-frequency generation study. <i>Applied Physics Letters</i> , 2016, 108, .	3.3	55

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19	Interaction between O ₂ and ZnO films probed by time-dependent second-harmonic generation. Applied Physics Letters, 2014, 104, .	3.3	8
20	Influence of the SiO ₂ interlayer thickness on the density and polarity of charges in Si/SiO ₂ /Al ₂ O ₃ stacks as studied by optical second-harmonic generation. Journal of Applied Physics, 2014, 115, .	2.5	54
21	Second-harmonic intensity and phase spectroscopy as a sensitive method to probe the space-charge field in Si(100) covered with charged dielectrics. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, 021103.	2.1	4
22	Influence of Surface Temperature on the Mechanism of Atomic Layer Deposition of Aluminum Oxide Using an Oxygen Plasma and Ozone. Langmuir, 2012, 28, 350-357.	3.5	54
23	Surface Reaction Mechanisms during Ozone and Oxygen Plasma Assisted Atomic Layer Deposition of Aluminum Oxide. Langmuir, 2010, 26, 13732-13735.	3.5	86